

Solstice[®] Metal Lift-Off and Photoresist Strip System

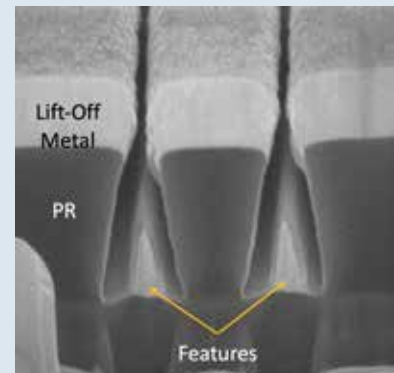
For Standard and More Aggressive Removal

Our Solstice[®] metal lift-off (MLO) and solvent strip system is a highly capable single-wafer automated solvent system. The chambers contain both a high-flow, low-pressure spray for 'soaking' applications as well as a high-pressure, programmable swing arm for more aggressive lift-off. This system is also capable of polymer removal. Fresh and reclaim solvent tanks, and inline heaters, provide fast and efficient solvation and stripping of organic films from the wafer. Our Solstice MLO process has been demonstrated on features below 1 micron in width.

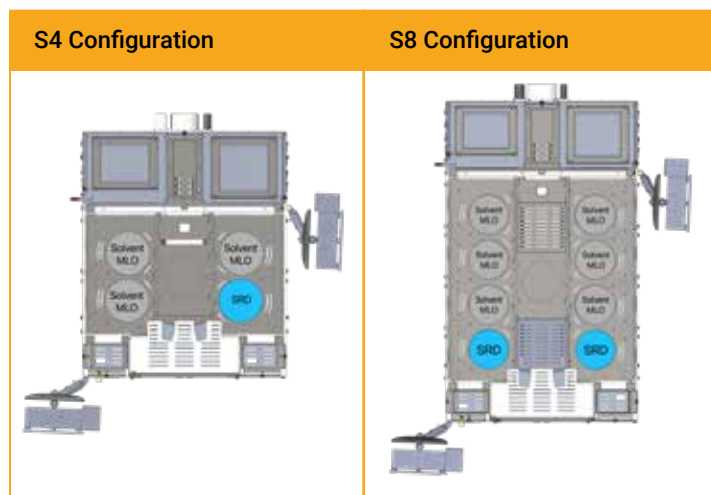
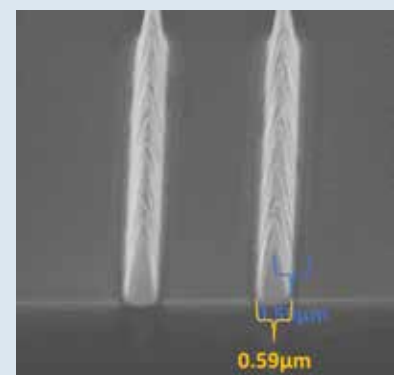
For safety, the face-down architecture of the solvent and MLO reactor prevents operator exposure to aggressive solvents unlike open chamber solvent systems. The chamber's annular exhaust allows for high-volume, low-velocity exhaust pull, minimizing chemistry loss during operation. An integrated fire suppression system and safety system also assures you the tool meets or exceeds all life-safety standards.



Before Metal Lift-Off



After Metal Lift-Off



Solstice configurations with multiple chambers can be paired with one or more SRD chambers.

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TECHNOLOGY

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